

Title (en)

Process and apparatus for decontamination using ion etching.

Title (de)

Verfahren und Vorrichtung zur Dekontaminierung durch Ionenätzen.

Title (fr)

Procédé et dispositif de décontamination par décapage ionique.

Publication

EP 0454584 B1 19950802 (FR)

Application

EP 91401101 A 19910425

Priority

FR 9005417 A 19900427

Abstract (en)

[origin: EP0454584A1] According to the invention, in order to decontaminate an object (2) whose surface is contaminated by a contaminating material, at least a part of the surface is covered with an enclosure (6), this part, taken as a target, is etched by cathodic sputtering and the contaminating material thus removed is collected on a substrate (12) contained in the enclosure. Application to the decontamination of objects contaminated with radioactive materials. <IMAGE>

IPC 1-7

G21F 9/00

IPC 8 full level

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CPC (source: EP)

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